Nanofluidics for Advanced Biomolecular Separations

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Third harmonic Nd-YAG(λ=355) exposure light
60 Hz pulse rate
50 mJ energy per pulse (IR power)
35 seconds exposure time (optimized)

1. Develop
2. Cr Deposition
3. Lift off
4. Plasma etching
5. Oxidization

\[ d = \frac{\lambda}{2 \times \sin \theta} \]

Large area chip
NanoT-Chip
MIR crystal

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